

PROCEEDINGS OF SPIE

# ***Advances in Metrology for X-Ray and EUV Optics VIII***

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**11–12 August 2019  
San Diego, California, United States**

*Sponsored and Published by*  
SPIE

**Volume 11109**

Proceedings of SPIE 0277-786X, V. 11109

SPIE is an international society advancing an interdisciplinary approach to the science and application of light.

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Author(s), "Title of Paper," in *Advances in Metrology for X-Ray and EUV Optics VIII*, edited by Lahsen Assoufid, Haruhiko Ohashi, Anand Asundi, Proceedings of SPIE Vol. 11109 (SPIE, Bellingham, WA, 2019) Seven-digit Article CID Number.

ISSN: 0277-786X  
ISSN: 1996-756X (electronic)

ISBN: 9781510629110  
ISBN: 9781510629127 (electronic)

Published by

**SPIE**

P.O. Box 10, Bellingham, Washington 98227-0010 USA  
Telephone +1 360 676 3290 (Pacific Time) · Fax +1 360 647 1445

[SPIE.org](http://SPIE.org)

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